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A virtual reactor for simulation of plasma enhanced chemical vapor deposition

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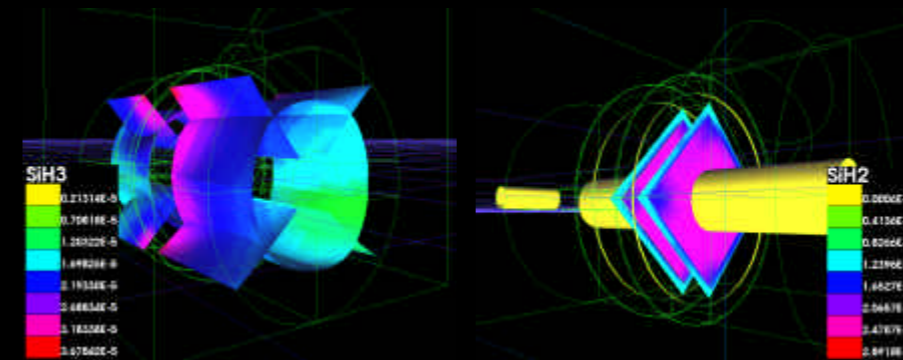
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A Virtual Reactor for Simulation of Plasma Enhanced Chemical Vapor Deposition

Valeria Krzhizhanovskaya

A Virtual Reactor for Simulation of Plasma Enhanced Chemical Vapor Deposition



Valeria Krzhizhanovskaya

Invitation

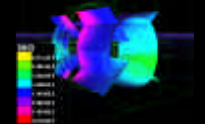
to attend the public
defense of my Ph.D. thesis

A Virtual Reactor for
Simulation of Plasma
Enhanced Chemical Vapor
Deposition

Friday, 20 June 2008
12:00

Agnietenkapel

Oudezijds Voorburgwal 231
Amsterdam



There will be a reception
after the ceremony

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